

Physics of semiconductor detectors operation at low temperatures

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Outline

- 1. General on semiconductor detectors**
- 2. S/B and P-I-N detectors**
- 3. Radiation effect in detectors**
- 4. Diamond properties**
- 5. Trapping time degradation in Diamond and Silicon**
- 6. Signal amplitude in Diamond and Silicon detectors**
- 7. Conclusions**

Back ground of PTI group which has been used in this presentation

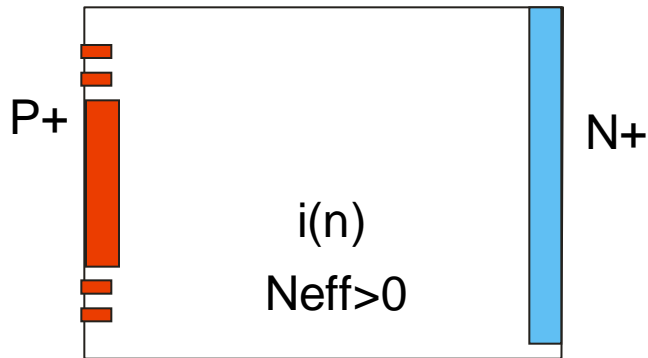
Performed R&Ds supported by international grants

1. CAST: R&D of **Transient Current Technique** for radiation hard detectors study (BNL).
2. ISTC: R&D of silicon **detectors array** for medical application (USA, for-profit company)
3. INTAS: R&D of radiation hard **cryogenic silicon detectors** (CERN-RD39 collaboration).
4. INTAS: R&D of silicon strip **detectors for ATLAS upgrade** (CERN-ATLAS).
5. INTAS: R&D of radiation hard **edgeless detectors** for TOTEM (CERN-TOTEM).
6. INTAS: R&D of spectrometric **DSSDs for EXL** (NuSTAR, FAIR).

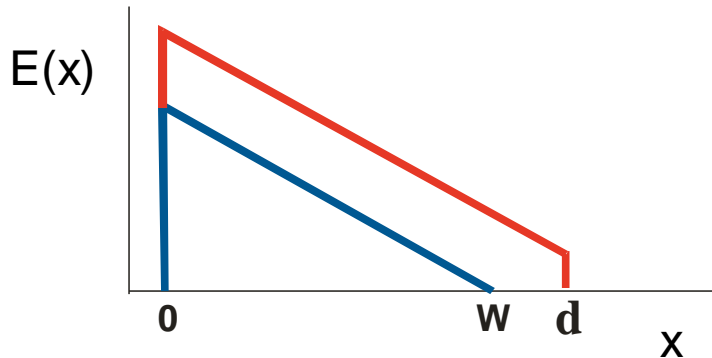
Development and Fabrication of Si detectors in the frame of international projects

- **Current injected detectors** for CERN-RD39 collaboration.
- P-on-N detectors for **“TECHNOTEST”** project of CERN-RD50 collaboration
- Reference **P-on-N baby detectors** for CERN-ATLAS strip detectors QA.
- **Full set of edgeless detectors** for CERN-TOTEM experiment.
- **New** : pre-series run of **radiation hard** silicon **edgeless** detectors for CERN-TOTEM upgrade.
- **Si strip spectrometric detectors** for NuSTAR experiment in FAIR program (GSI)

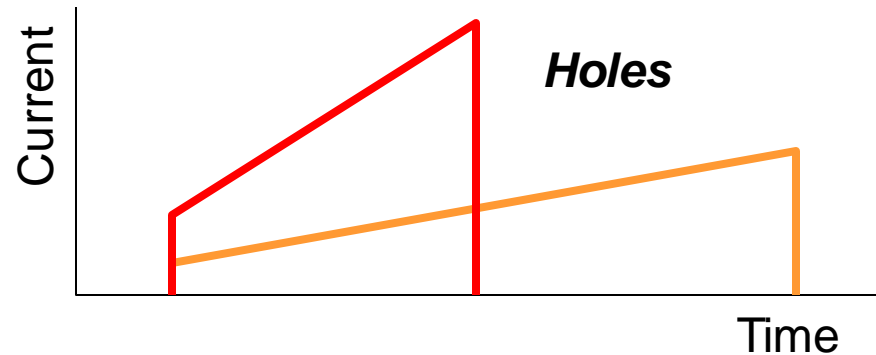
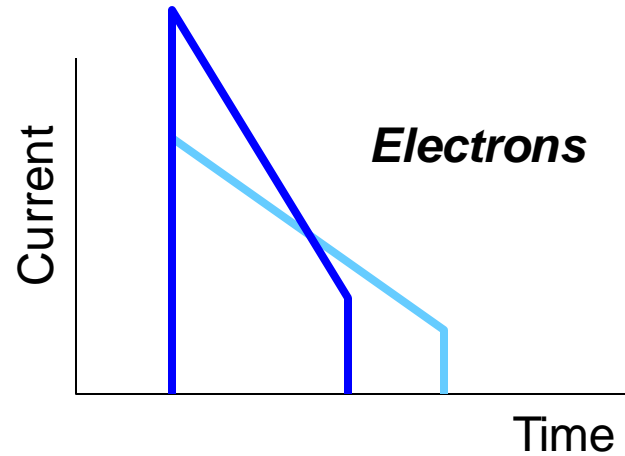
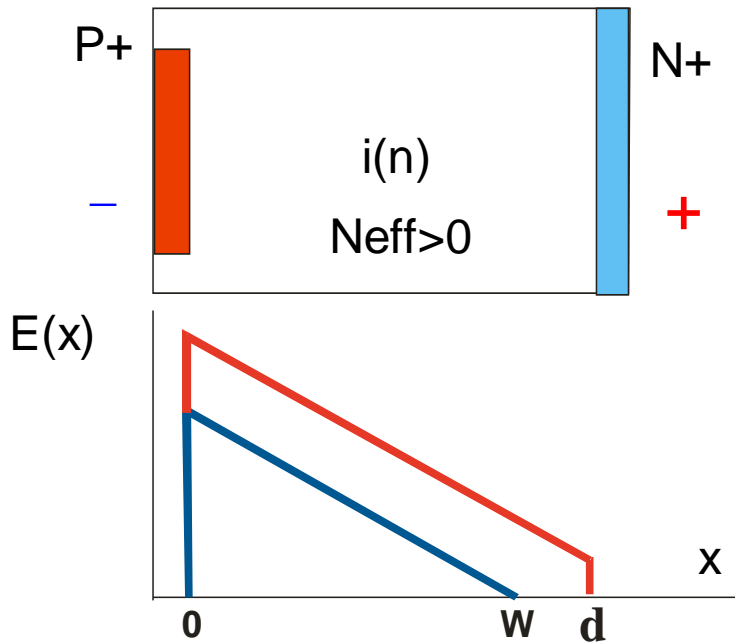
Si planar detector, static



Electron mobility ... 1500 cm²/v s
Hole mobility 450 cm²/v s
 V_{sat} 1 10⁷ cm/s
 d 300 μm
 N_{eff} 1 10¹² cm⁻³
 V_{fd} 30-100 V
 V_{op} 100-300 V
 $\langle E \rangle$ 1 10⁴ v/cm



Si PAD detector response



$$J = 1/d \times q \mu E$$

Drift time ... 3 – 50ns

TCT data (830 nm laser)

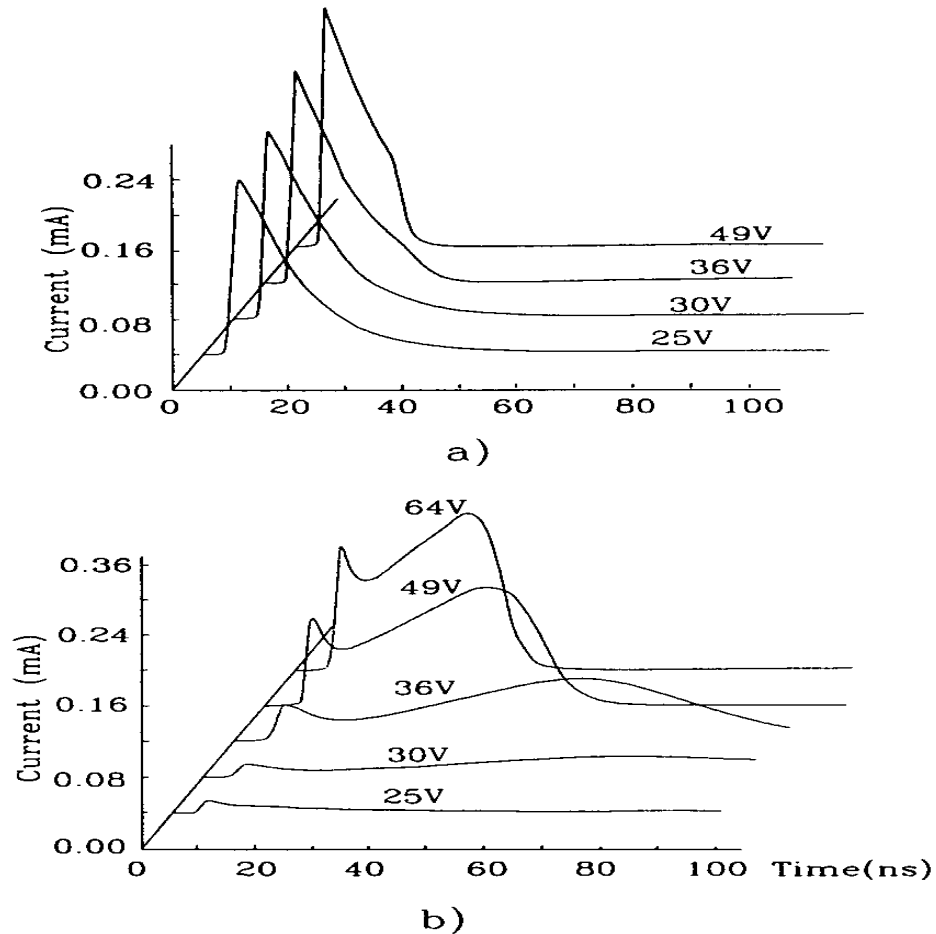
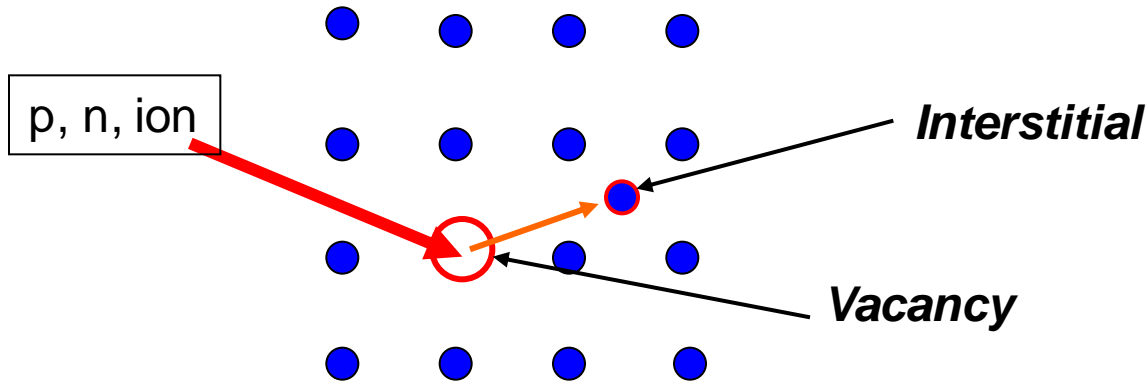


Fig. 9. A set of current pulses before and after depletion voltage for a deep level free detector: non-equilibrium carriers are generated (a) near the front p^+ -contact (drift of electrons); (b) near the back n^+ -contact (drift of holes).

Effect of irradiation on detector



Primary defects (Frenkel pairs): vacancy (V) and interstitial (I)

Secondary defects:

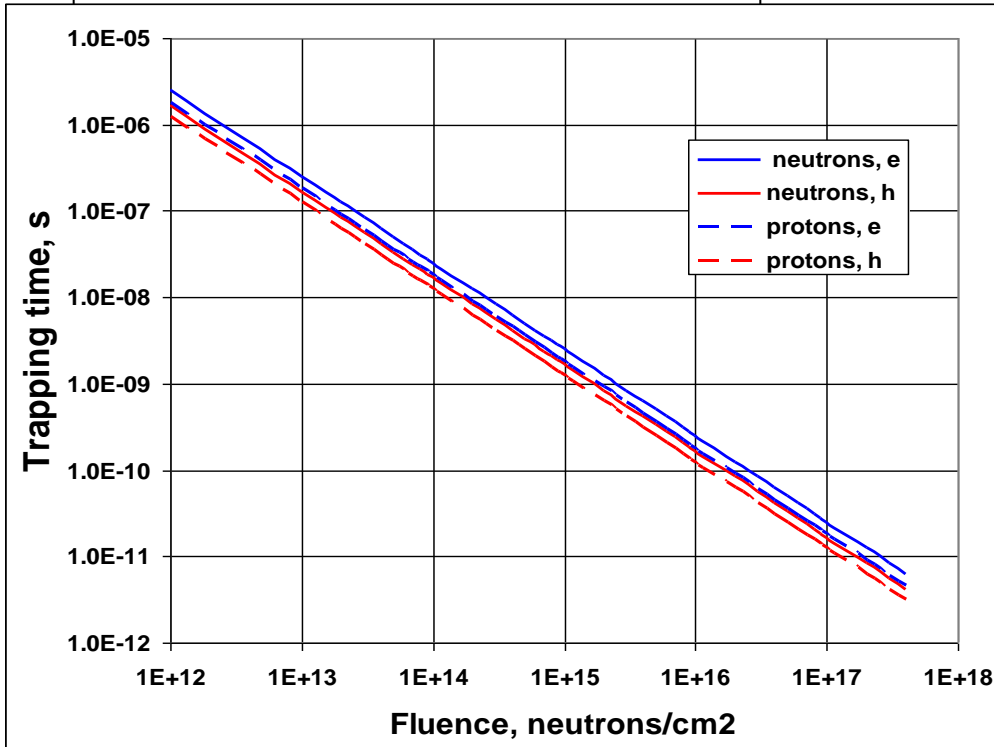
Divacancy - V + V

A center - V + O

E center - V + P

Life time degradation in Si

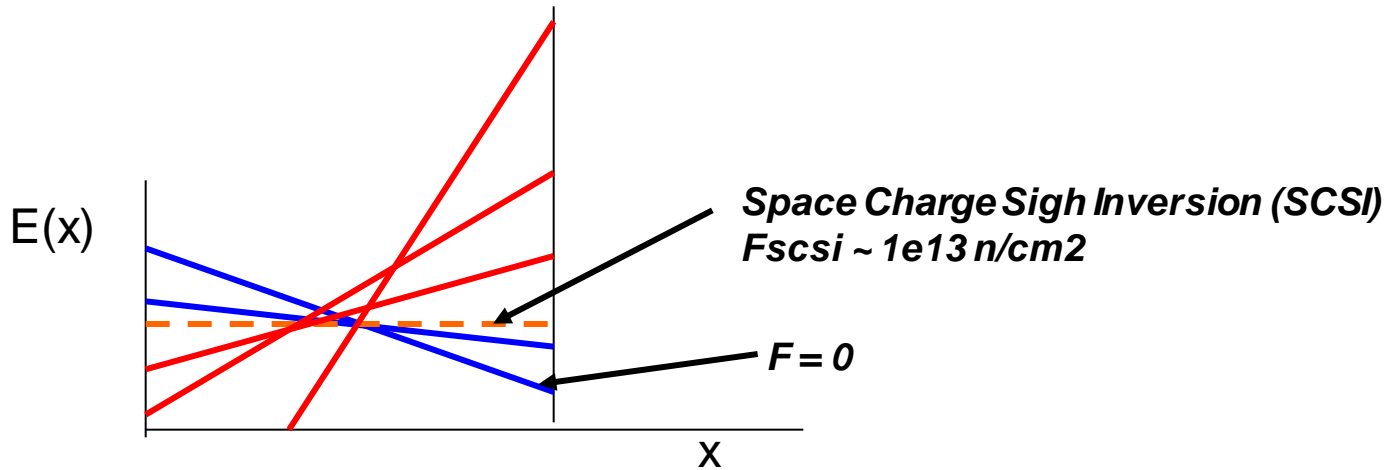
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$$\tau(\phi) = (1/\tau_0 + \beta\phi)^{-1}$$

Trapping probability (protons)	
τ_e^0	1×10^3
β_e	5.5×10^3
τ_h^0	1×10^3
β_h	8×10^3

Electric field evolution in Si detectors with fluence (simple model)



Basic formulas

- Charge Collection Distance (CCD)

$$CCD = V_{dr} \times T_{tr}$$

- Trapping time

$$T_{tr} = (\sigma \times V_{th} \times N_{tr})^{-1}$$

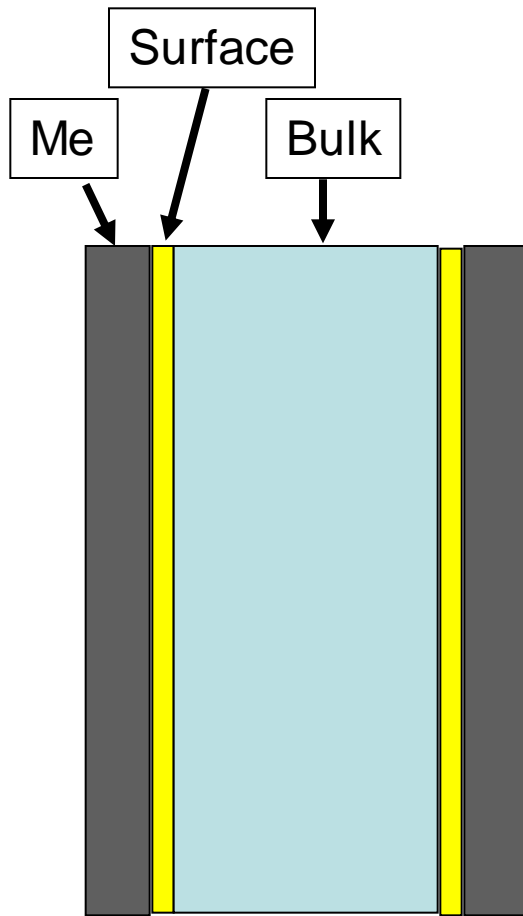
- *Detrapping time*

$$T_{dtr} = [(\sigma \times V_{th} \times N_c \times \exp(-E_{act}/kT))]^{-1}$$

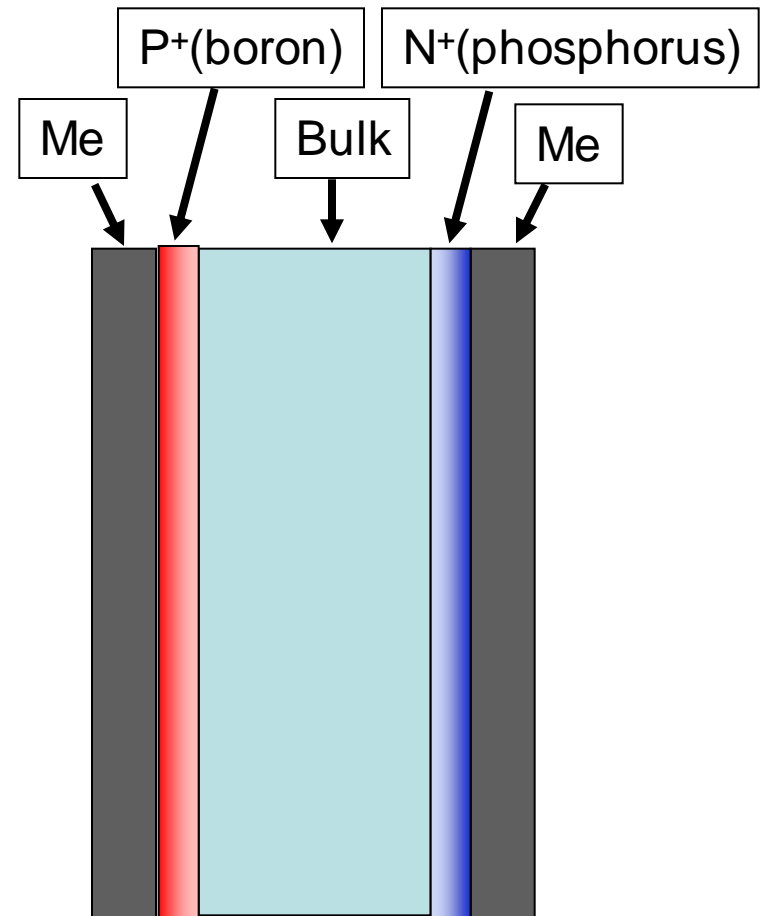
- *Width of the depleted layer in P-N junction*

$$W = \left(\frac{\epsilon \epsilon_o \cdot V}{2\pi q_e^2 N_{eff}} \right)^{\frac{1}{2}}$$

Comparison of Surface-barrier and P-I-N detectors

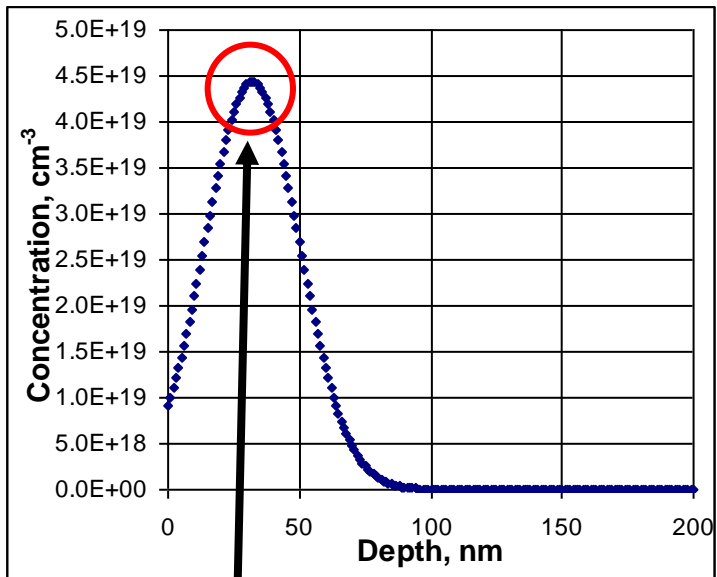


S/B detector
or M-S-M

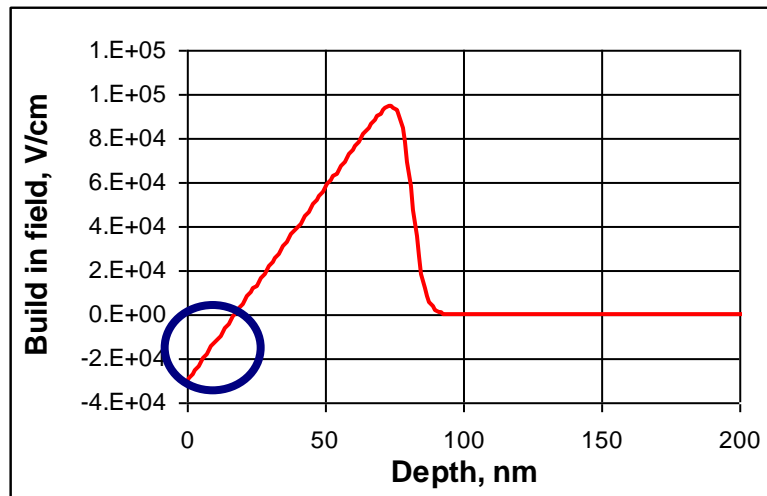
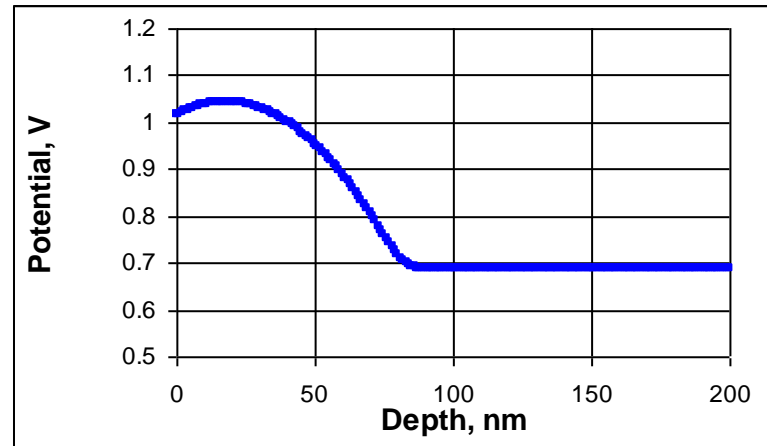


P-I-N

Electric field and potential at the detector entrance window



Degenerate Silicon
Si=Me



Comparison of S/B and P-I-N detectors

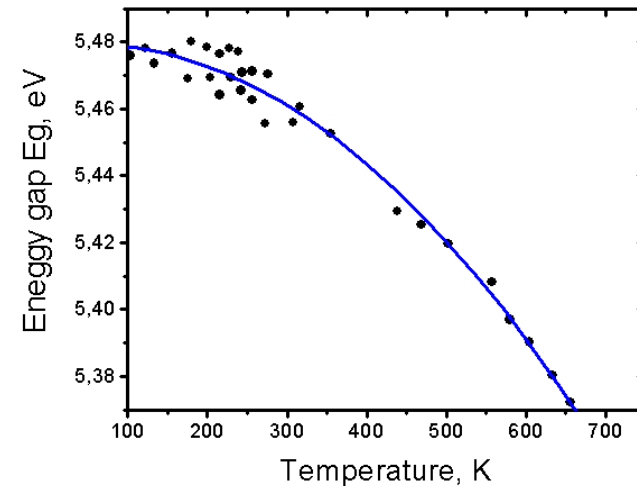
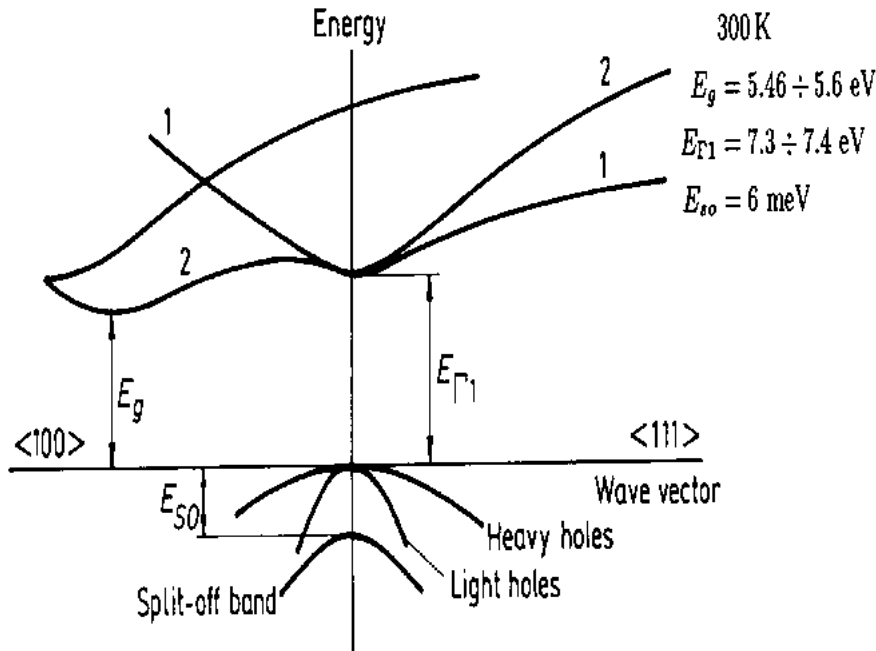
S/B

- **Hardly controlled surface properties,**
- **Low reproducibility of S/B contact,**
- **Complicate technology,**
- **Oxidized surface or damaged interface prevents charge flow from the bulk to metal contact,**
- **High probability for charge accumulation at the interface and detector polarization,**
- **Unpredictable scenario of long term detector stability,**
- **Problem for operation at high current density,**
- **Optimal for low T operation in case the mentioned above problems will be solved.**

P-I-N

- **Reproducible technology,**
- **Smooth transition between bulk and me contact**
- **No interface between Si and Metal contact**
- **No chance accumulate charge at the surface**
- **No polarization,**
- **Requires more study for low T operation mainly for highly doped regions.**

Band diagram for Diamond



$N_c \sim 10^{20} \text{ cm}^{-2}$

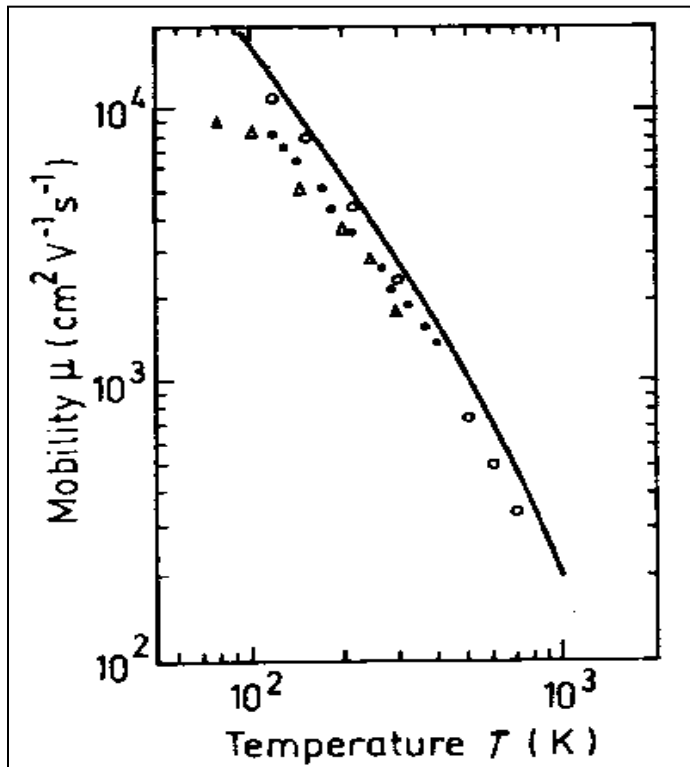
$N_v \sim 10^{19} \text{ cm}^{-2}$

$N_i \sim 10^{-27} \text{ cm}^{-2}$

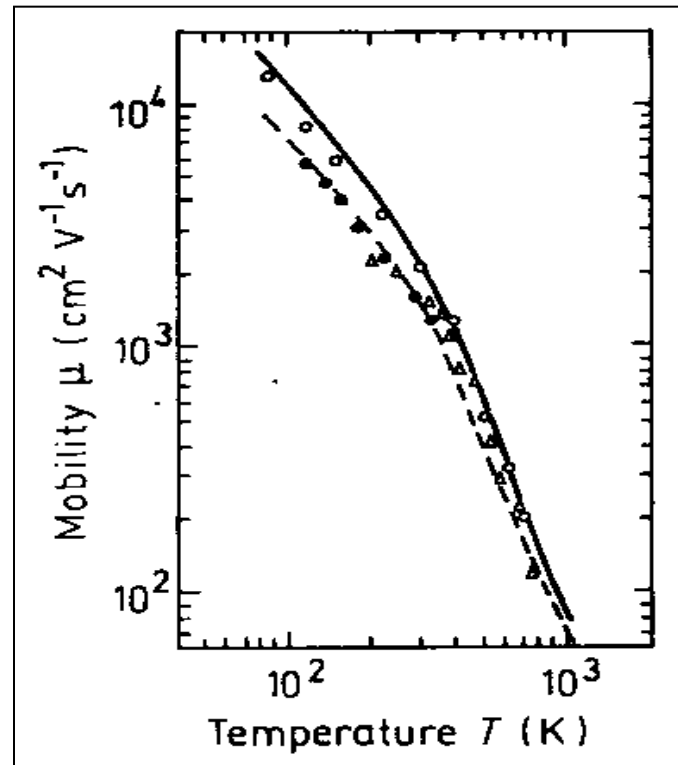
Band diagram depends in the crystal axes – anisotropy of parameters is expected

Mobility in natural diamond

electrons

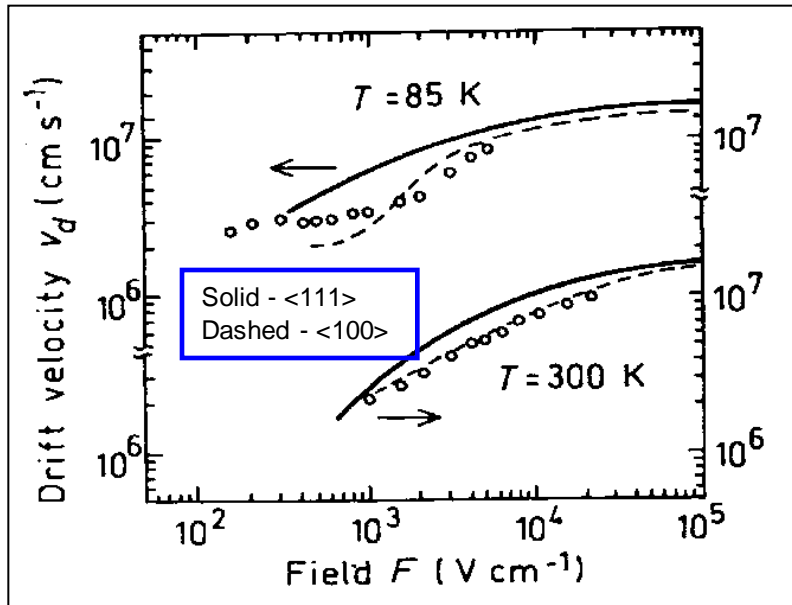


holes

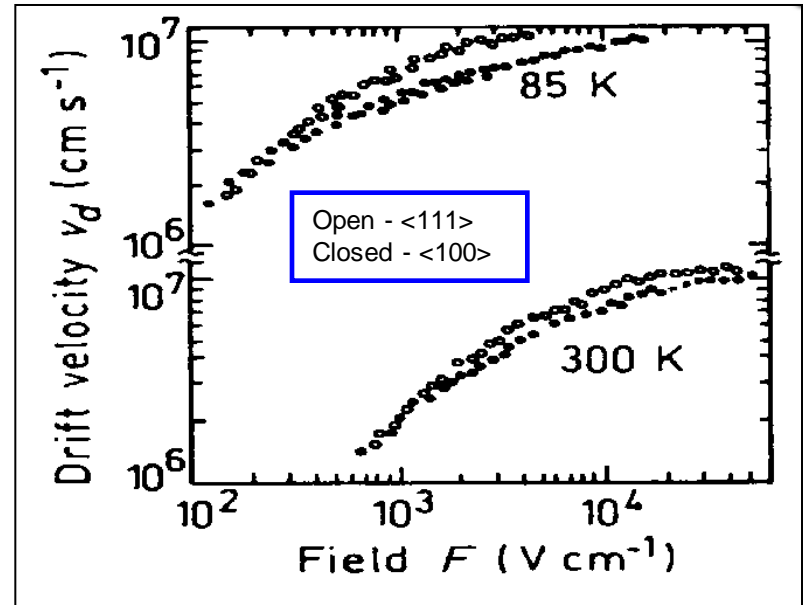


Anisotropy of drift velocity

electrons

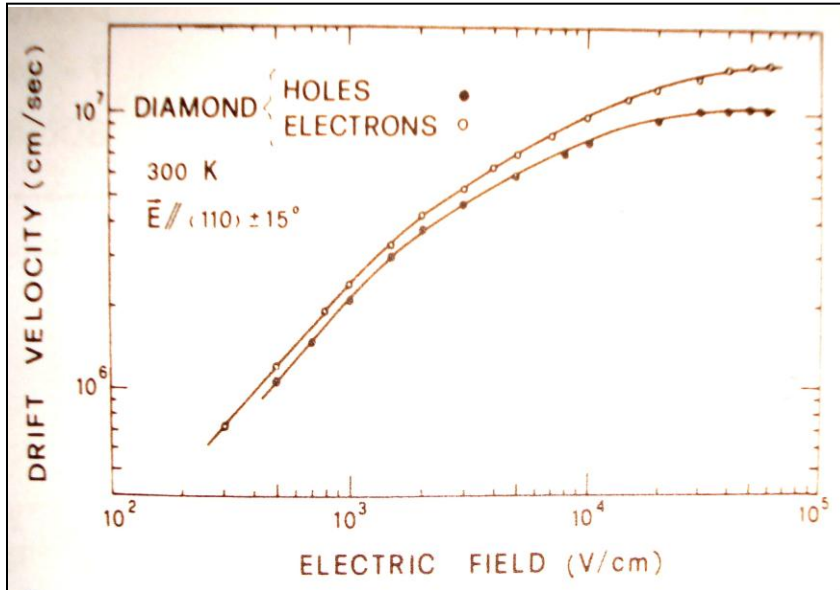


holes

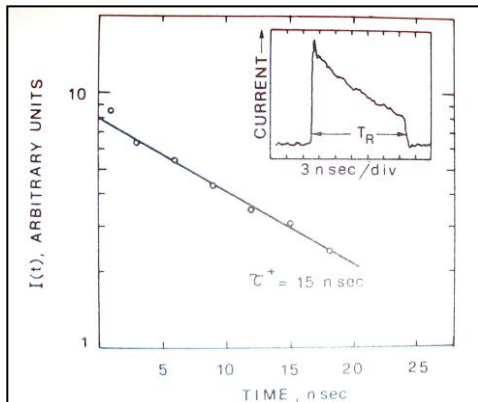
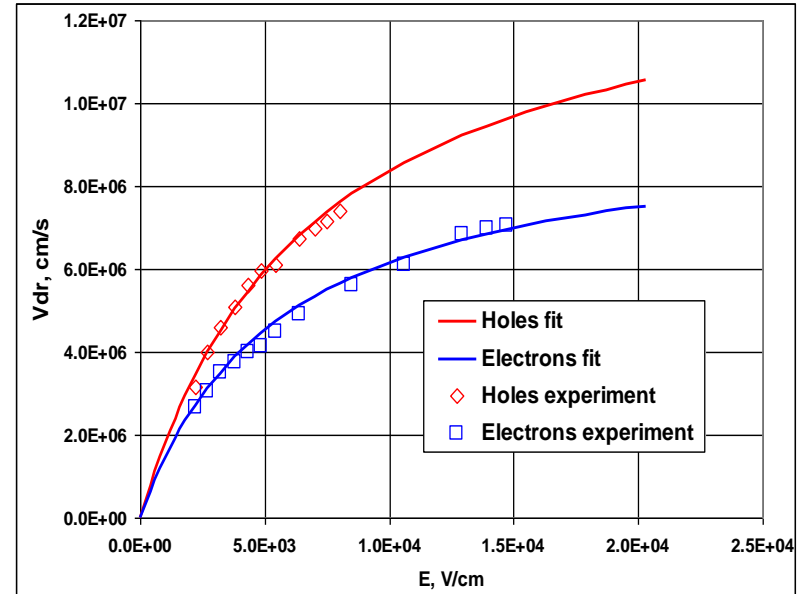


Drift velocity in modern Diamond

Natural



sc-CVD



	holes	electrons
μ_0 , cm/Vs	2100	2400
V_s , cm/s	$1.05E+07$	$1.50E+07$

	holes	electrons
μ_0 , cm/Vs	2064	1714
V_s , cm/s	$1.41E+07$	$9.60E+06$

From C.Canali,
NIM 160 (1979) p. 73-77

$$V_{dr} = \mu_0 E / (1 + \mu_0 E / V_s)$$

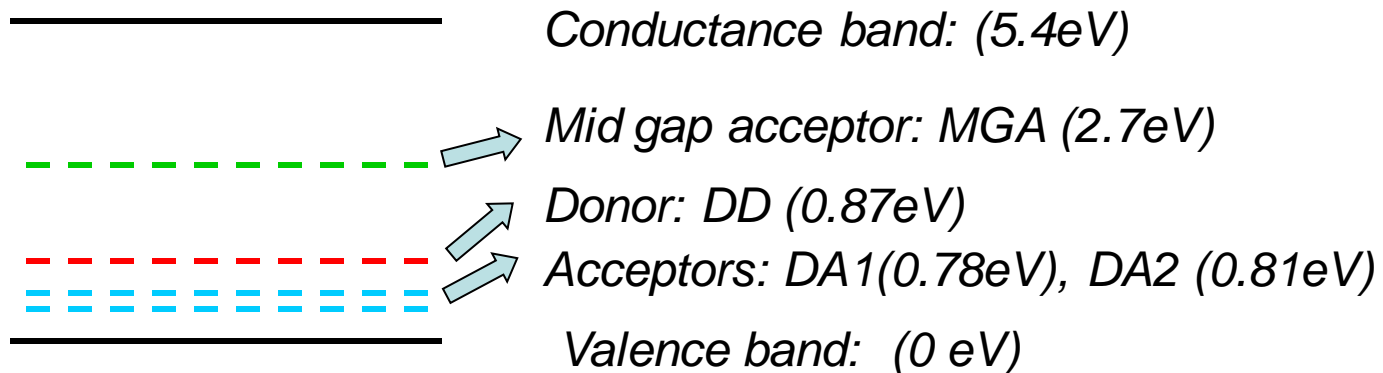
Effect of drift velocity anisotropy ???

Deep levels in CVD diamond

- INFN - Florence) model

Proofed by :thermal stimulated current measurements – TSC and PICTS

Photoconductivity measurements



What does this model define ??

Trends in the improvement of CVD diamond technology

DL's concentration

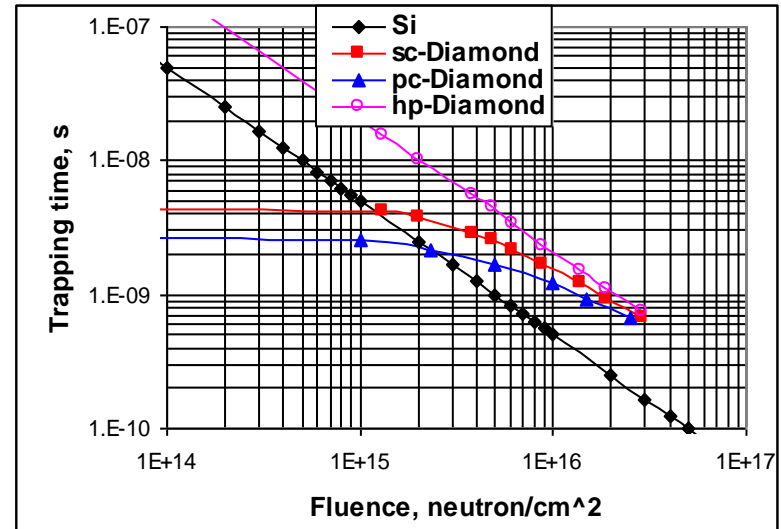
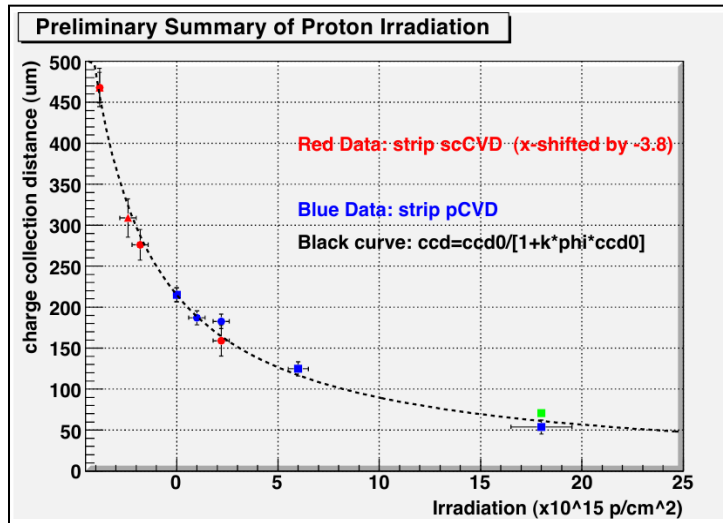
Years	1998	2000
MGA , cm ⁻³	5x10 ¹⁵	2.5x10 ¹⁵
DD , cm ⁻³	5x10 ¹⁵	2.5x10 ¹⁵
DA1 , cm ⁻³	3x10 ¹⁴	4x10 ¹³
DA2 , cm ⁻³	6x10 ¹³	2x10 ¹³

Bulk diamond parameters

E_f , eV	0.935	0.964
n , cm ⁻³	1.84x10 ⁻⁵⁷	5.8x10 ⁻⁵⁷
p , cm ⁻³	8.61x10 ²	2.68x10 ²
ρ , Ohm cm	4x10 ¹²	1.27x10 ¹³
+N_{tr} (e) , cm ⁻³	3.57x10 ¹⁴	5.99x10 ¹³
-N_{tr} (h) , cm ⁻³	3.58x10 ¹⁴	5.99x10 ¹³
N_{tr}eff , cm ⁻³	7.15x10 ¹⁴	1.2x10 ¹⁴

- ***Diamond is a p-type semiconductor***
- ***Purification leads to:***
 - ✓ Decrease of Fermi level
 - ✓ Increase of resistivity
 - ✓ Increase of trapping

Trapping in irradiated Si and Diamond



From:
W.Trischuk & RD42,
Resent advances in diamond detectors

Conclusion:
Trapping time degradation rate:
Silicon $\beta = 2e-7$ cm²/s
Diamond $\beta = 7.5e-7$ cm²/s

Conditions for comparison:

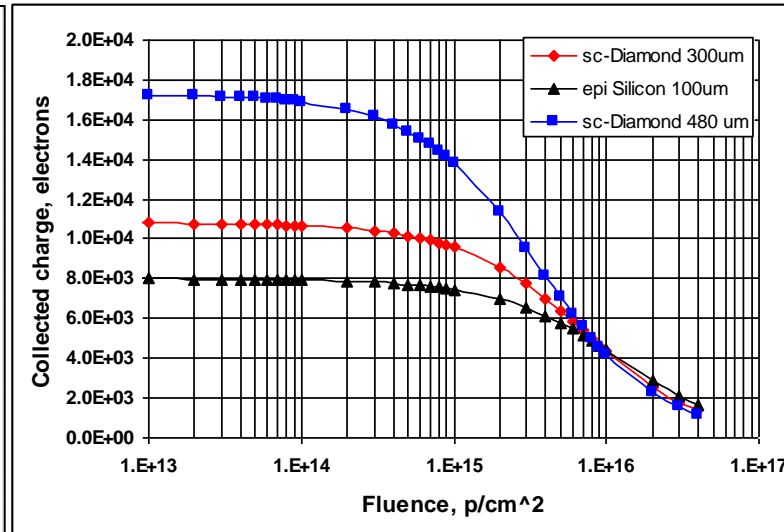
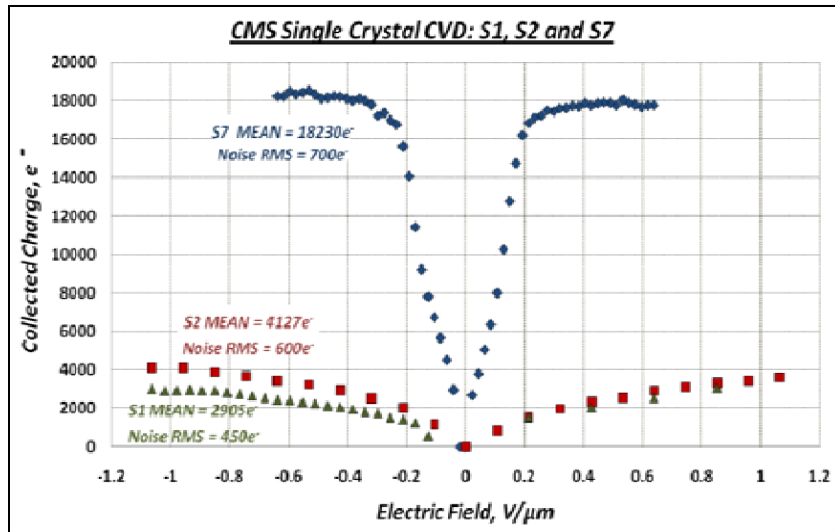
Electric field 1V/um
Diamond SC and PC
Silicon MC
Diamond irradiated by protons 24GeV
Silicon irradiated by protons 24GeV

$$CCD = Vdr \cdot T$$

$$T \sim 1/Ntr$$

$$Ntr \sim F$$

Absolute signal in Si and Diamond PAD detectors (trapping time degradation effect)



From “Fast beam conditions monitoring (BCM1F) for CMS” by N/Bernardino Rodrigues, ...

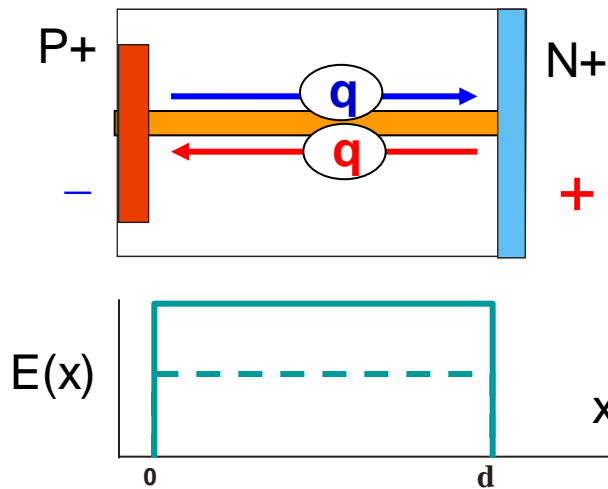
$V_b = 300V$

sc-Diamond, 480um
 at $F_p = 1.75e^{15} \text{ 1/cm}^2$
 $Q_{coll} (S1) = 2900e$ and
 $Q_{coll} (S2) = 4130e$!!!
 Expected > 10000e

Parameters

Uniform electric field
 temperature - 290K
 $d(1/\tau)/dF$ silicon - $2e-7 [s^{-1} \cdot cm^2]$
 $d(1/\tau)/dF$ diamond - $7.5e-8 [s^{-1} \cdot cm^2]$

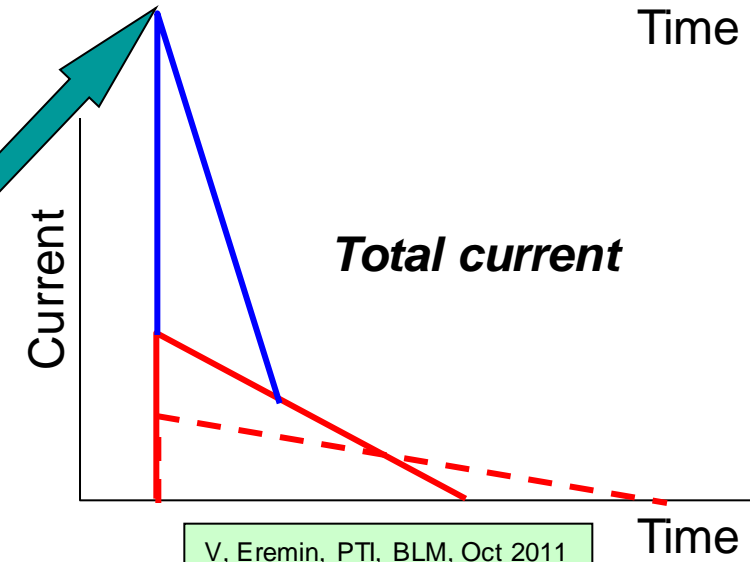
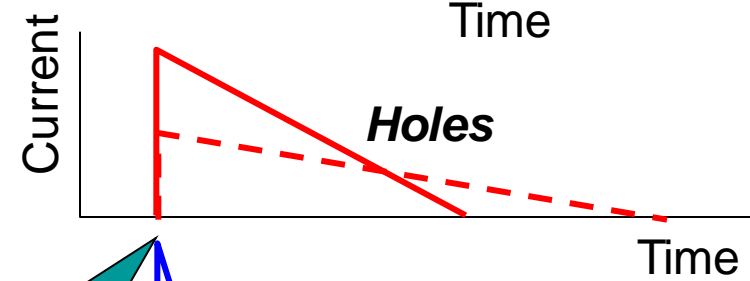
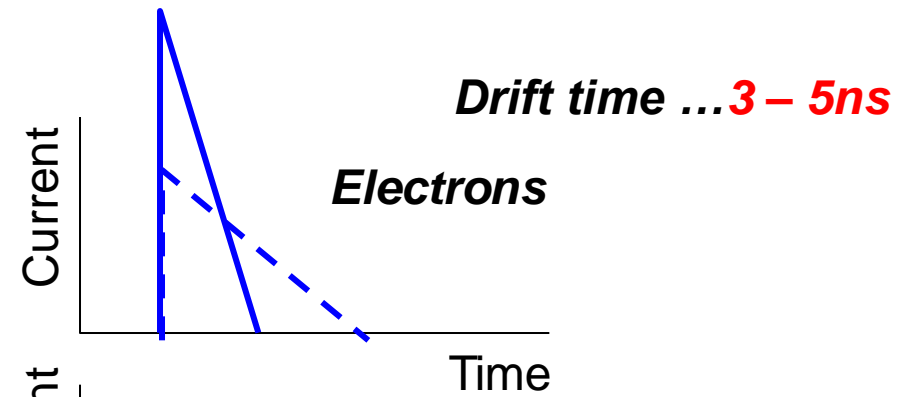
Current response of pad semiconductor detector (MIPs)



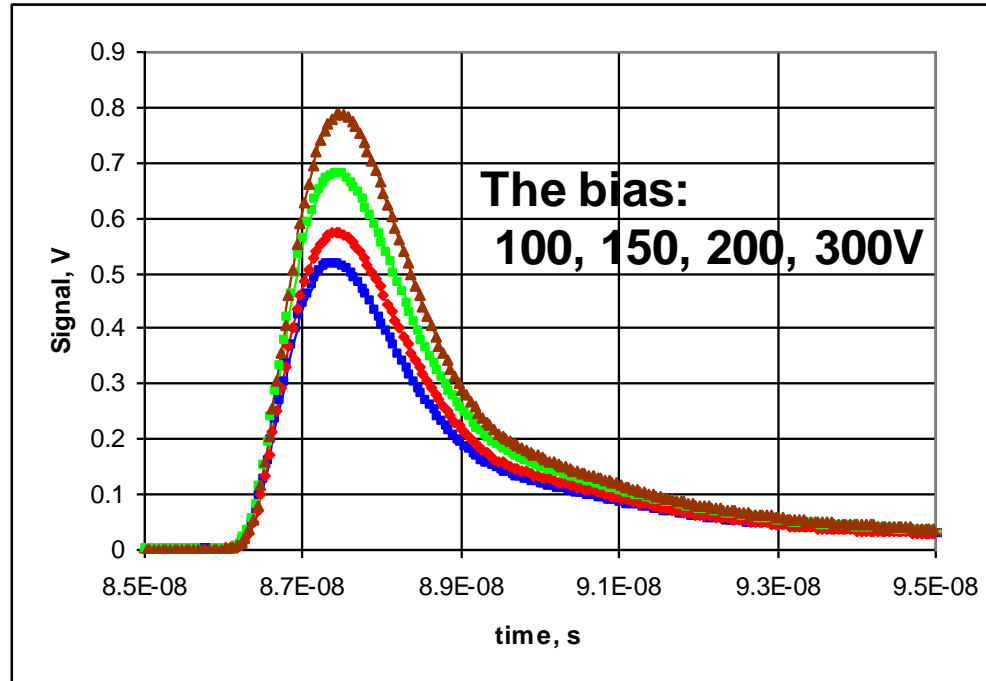
$d \dots\dots 300\mu\text{m}$
 $N_{\text{eff}} \dots\dots 10^{11}\text{cm}^{-3}$
 $V_{\text{fd}} \dots\dots < 20\text{V}$
 $V_{\text{op}} \dots\dots 100\text{-}300\text{V}$

$$J_{\text{max}} = 1/d q(Gd\mu_e E + Gd\mu_h E) = qG(\mu_e E + \mu_h E) = qG(v_e + v_h)$$

G – pair generation rate, 1/cm



MIP current response for Si detector



Detector thickness - 300 μm
MIP detection (Laser 1060 nm)
Rise time - 600 ps (defined by electronics)
Expected time resolution <100 ps

Si and Diamond

Parameter		Silicon	pc-Diamond	sc-Diamond
Z		14	6	6
A		28.1	12	12
Density		2.329	3.515	3.515
Band width, eV		1.12	5.48	5.48
Pair creation energy, eV		3.63	13.1	13.1
Permittivity		11.9	5.7	5.7
Resistivity, kOhm cm		<100	>1e10	>1e10
Drift mobility, cm ² /V/s	h	505	1000	2400
	e	1450	1800	1900
Saturation velocity, cm/s	h	8.4e6	1e7 ?	
	e	1e7	2e7 ?	
MIP pair generation density, cm ⁻¹		0.9e6	0.36e6	
MIP response amplitude, A		1.5e-6	1e-6	
Life/trapping time, ns		1e7	1 – 10	40
Charge collection distance, um		100000	< 200	> 500

Conclusions

1. **Many physical parameters for Diamond are still not precisely defined: V_{dr} , mobility, V_s , trapping related parameters.**
2. **Shallow level impurities are not discovered for Diamond that makes impossible fabricate P-i-N structures.**
3. **Trapping time degradation is much less then for Silicon however the high density of defects and impurities limits the trapping time at the level equivalent of of flence $>1e15$ p/cm²**
4. **Polarization could be a major unpredictable factor of Diamond detector operation in DC current mode at low temperatures.**

Thank you for your attention